



FORM 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No. KLA1P058 Applicant: Han et al. Filing Date 1/28/02	Application No.: 10/058,614 Group 2862-2829
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U.S. Patent Documents

Foreign Patent or Published Foreign Patent Application

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
VN	A1	T. P. Chang et al., "Arrayed miniature electron beam columns for high throughput sub-100 nm lithography", J. Vac. Sci. Technol. B, Vol. 10, No. 6, Nov./Dec. 1992, pp. 2743-2747.
VN	A2	E. Yin et al., "Electron optical column for a multicolumn, multibeam direct-write electron beam lithography system", J. Vac. Sci. Technol. B, Vol. 18, No. 6, Nov./Dec. 2000, pp.3126-3131.
VN	A3	T. R. Groves et al., "Distributed, multiple variable shaped electron beam column for high throughput maskless lithography", J. Vac. Sci. Technol. B, Vol. 16, No. 6, Nov./Dec. 1998, pp. 3168-3173.

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.